

AMENDMENTS TO THE CLAIMS:

1. (Original) A method of forming a coating comprising:
 - providing a substrate having a metal layer;
 - applying an antireflective layer to said substrate layer;
 - applying an insulator layer to said antireflective layer; and
 - applying a lubrication layer to said insulator layer.
2. (Original) The method of Claim 1, said applying an insulator comprising:
 - applying an oxide layer over said antireflective layer.
3. (Original) The method of Claim 1, said applying an insulator comprising:
 - applying an oxide layer over said antireflective layer using plasma deposition.
4. (Original) The method of Claim 1, said providing comprising:
 - providing a partially fabricated micromechanical device.
5. (Original) The method of Claim 1, said providing comprising:
 - providing a partially fabricated micromechanical device having an electrode.
6. (Original) The method of Claim 1, said providing comprising:
 - providing a partially fabricated micromechanical device having an aluminum alloy electrode.
7. (Original) The method of Claim 1, said providing comprising:
 - providing a partially fabricated micromirror device comprising an aluminum alloy landing electrode supported by a semiconductor substrate.
8. (Original) The method of Claim 7, said applying an antireflective coating comprising:
 - applying a titanium nitride coating to said landing electrode.
9. (Original) The method of Claim 8, said applying an insulator layer comprising:
 - applying an oxide layer over said titanium nitride coating.

10. (Original) The method of Claim 8, said applying an insulator layer comprising:
applying an oxide layer over said titanium nitride coating using plasma deposition.
11. (Original) The method of Claim 8, said applying an insulator layer comprising:
growing a thermal oxide layer over said titanium nitride coating.
12. (Original) The method of Claim 9, said applying a lubrication layer comprising:
applying a halogenated acid layer to said oxide layer.
13. (Original) The method of Claim 9, said applying a lubrication layer comprising:
applying a perfluorodecanoic acid layer to said oxide layer.
14. (Original) The method of Claim 1, said applying an insulator layer comprising:
applying a metal layer over said antireflective layer; and
oxidizing said metal layer.
15. (Original) The method of Claim 1, said applying an insulator layer comprising:
applying a metal layer no thicker than 200Å over said antireflective layer; and
oxidizing said metal layer.
16. (Original) The method of Claim 1, said applying an insulator layer comprising:
applying a metal layer no thicker than 100Å over said antireflective layer; and
oxidizing said metal layer.
17. (Original) The method of Claim 1, said applying an insulator layer comprising:
applying an aluminum layer no thicker than 100Å over said antireflective layer;
and
oxidizing said metal layer.
18. (Original) The method of Claim 1, said applying a lubrication layer comprising:

applying a halogenated acid layer to said insulator layer.

19. (Original) The method of Claim 1, said applying a lubrication layer comprising:

applying a perfluorodecanoic acid layer to said insulator layer.

20. (Original) A micromechanical device comprising:

a substrate;

a reflective member supported on said substrate;

an antireflective coating supported on said reflective member;

an insulator layer supported on said antireflective coating; and

a lubrication layer supported on said insulator layer.

21. (Original) The micromechanical device of Claim 20, said substrate comprising:

a silicon substrate.

22. (Original) The micromechanical device of Claim 20, said reflective member comprising:

an aluminum alloy member supported on said substrate.

23. (Original) The micromechanical device of Claim 20, said reflective member comprising:

an aluminum alloy landing electrode supported on said substrate.

24. (Currently amended) The micromechanical device of Claim 20, said antireflective coating comprising:

a titanium nitride coating supported on said substrate reflective member.

25. (Currently amended) The micromechanical device of Claim 20, said insulator layer comprising:

an oxide layer supported on said substrate antireflective coating.

26. (Currently amended) The micromechanical device of Claim 20, said insulator layer comprising:

an oxide layer plasma deposited on said substrate antireflective coating.

27. (Currently amended) The micromechanical device of Claim 20, said insulator layer comprising:

an thermal oxide layer grown on said substrate antireflective coating.

28. (Original) The micromechanical device of Claim 20, said lubrication layer comprising:
a halogenated acid layer supported on said insulator layer.

29. (Original) The micromechanical device of Claim 20, said lubrication layer comprising:
a perfluorodecanoic acid layer supported on said insulator layer.

30. (Original) A system comprising:

a light source for providing a beam of light along a light path; and
a device on said light path, said device comprising:

a substrate;

a reflective layer;

an antireflective coating supported on said reflective layer;

an insulation layer supported on said antireflective coating; and

a lubrication layer on said insulation layer.

31. (Original) The system of Claim 30, said substrate comprising:

a silicon substrate.

32. (Original) The system of Claim 30, said reflective member comprising:
an aluminum alloy member supported on said substrate.

33. (Original) The system of Claim 30, said reflective member comprising:
an aluminum alloy landing electrode supported on said substrate.

34. (Currently amended) The system of Claim 30, said antireflective coating comprising:

a titanium nitride coating supported on said substrate reflective layer.

35. (Currently amended) The system of Claim 30, said insulator layer comprising:

an oxide layer supported on said substrate antireflective coating.

36. (Currently amended) The system of Claim 30, said insulator layer comprising:

an oxide layer plasma deposited on said substrate antireflective coating.

37. (Currently amended) The system of Claim 30, said insulator layer comprising:

an thermal oxide layer grown on said substrate antireflective coating.

38. (Original) The system of Claim 30, said lubrication layer comprising:

a halogenated acid layer supported on said insulator layer.

39. (Original) The system of Claim 30, said lubrication layer comprising:

a perfluorodecanoic acid layer supported on said insulator layer.